

WHAT IS CLAIMED IS:

1. A method for treating perfluorocompounds, which comprises a step of decomposing perfluorocompounds contained in a gas and a step of sucking a discharged gas containing acid gases resulting from the decomposition of the perfluorocompounds by a jet stream of an injected gas, thereby ejecting the sucked gas.
2. A method for treating perfluorocompounds, which comprises a step of decomposing perfluorocompounds contained in a gas, a step of bringing the discharged gas containing acid gases resulting from the decomposition of the perfluorocompounds into contact with one of water and an aqueous alkaline solution, thereby removing the acid gases from the discharged gas, a step of separating mists contained in the discharged gas after the contact with one of the water and the aqueous alkaline solution, and a step of sucking the discharged gas separated from the mists by a jet stream of an injected gas, thereby ejecting the sucked gas.
3. A method according to Claim 1, wherein the perfluorocompounds are catalytically decomposed.
4. A method according to Claim 1, wherein the step of sucking the discharged gas by a jet stream of the injected gas, thereby ejecting the sucked gas is carried out by an ejector.
5. A method for treating a discharged gas from a semiconductor production plant, which comprises a step

6. A method for treating a discharged gas from a semiconductor production plant, which comprises a step of decomposing perfluorocompounds contained in a discharged gas from a semiconductor production plant, a step of bringing the discharged gas containing acid gases resulting from the decomposition of the perfluorocompounds into contact with one of water and an aqueous alkaline solution, thereby removing the acid gases from the discharged gas, a step of separating mists contained in the discharged gas after the contact with one of the water and the aqueous alkaline solution, and a step of sucking the discharged gas separated from the mists by a jet stream of an injected gas, thereby ejecting the sucked discharged gas.

8. A method according to Claim 5, wherein the discharged gas is sucked by the jet stream of the injected gas and ejected by an ejector.

9. An apparatus for treating perfluorocompounds, which comprises a perfluorocompounds decomposing apparatus for decomposing perfluorocompound contained

in a gas fed thereto, and a gas suction apparatus for sucking the discharged gas containing acid gases resulting from the decomposition of the perfluorocomopunds by a jet stream of an injected gas, thereby ejecting the gas.

10. An apparatus for treating perfluorocompounds, which comprises a perfluorocompounds decomposing apparatus for decomposing perfluorocompounds contained in a gas fed thereto, an acid gas removing apparatus for removing acid gases resulting from the decomposition of the perfluorocompounds from the discharged gas, and a gas suction apparatus for sucking the discharged gas in the acid gas removing apparatus by a jet stream of an injecting gas, thereby ejecting the gas.

11. An apparatus according to Claim 10, wherein the acid gas removing apparatus is carried out by bringing the discharged gas containing the acid gases into contact with one of water and an aqueous alkaline solution, thereby removing the acid gases from the gas, and a mist separation apparatus for separating mists from the gas discharged from the acid gas removing apparatus by suction by the gas suction apparatus is further provided.

12. An apparatus according to Claim 11, wherein tank for receiving one of the water and the aqueous alkaline solution from the acid gas removing apparatus and a discharging piping leading the mists separated in

TOP SECRET-148607660

the mist separating apparatus to the tank are further provided below the acid gas removing apparatus and the mist separating apparatus.

13. An apparatus according to Claim 9, wherein the perfluorocompound decomposing apparatus is packed with a catalyst acting to decompose the perfluorocompounds.

14. An apparatus according to Claim 13, wherein the catalyst contains an Al oxide and further one oxides of metals selected from Zn, Ni, Ti, F, Sn, CO, Zr, Ce, Si and Pt.

15. An apparatus according to Claim 9, wherein the gas suction apparatus is an ejector.

16. An apparatus according to Claim 15, wherein a means of stopping feeding of driving gas to the ejector, when the pressure of the driving gas to the ejector exceeds a set pressure is further provided.

706230-73607600